

Docket No.: MUH-12818



IPW

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By:

Date: July 22, 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applic. No. : 10/675,049 Confirmation No: 5871
Applicant : Ioannis Dotsikas
Filed : September 30, 2003
Title : Method and Furnace for the Vapor Phase Deposition of
Components onto Semiconductor Substrates with a Variable
Main Flow Direction of the Process Gas
Art Unit : 2818
Examiner : Renee R. Berry
Docket No. : MUH-12818
Customer No. : 24131

R E S P O N S E

Hon. Commissioner for Patents

Sir:

Responsive to the Office Action dated June 30, 2004, the following remarks are made:

In deference to the restriction requirement on pages 2 and 3 of the above-identified Office Action, applicant elects group II, claims 13-17, for prosecution at this time.

Applicant requests a rejoinder under MPEP §821.04.

In view of the foregoing, the early issuance of an Action on the merits of claims 13-17 is solicited.

Respectfully submitted,

For Applicant

Date: July 22, 2004

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